

	L #	Hits	Search Text	DBs	Time Stamp
1	L1	7163	(427/526,531,562,564,595,96,77,123,125).CC LS.	USPA T; US-P GPUB ; EPO; JPO; DERW ENT; IBM TDB	2003/09/0 9 15:20
2	L2	4443	(438/584,652,622,650,666,674,685,686,688).CCLS.	USPA T; US-P GPUB ; EPO; JPO; DERW ENT; IBM TDB	2003/09/0 9 15:22
3	L3	5880	FIB focused adj ion adj beam	USPA T; US-P GPUB ; EPO; JPO; DERW ENT; IBM TDB	2003/09/0 9 15:23
4	L4	67	(1 or 2) and 3	USPA T; US-P GPUB ; EPO; JPO; DERW ENT; IBM TDB	2003/09/0 9 15:24

10/084,688

	L #	Hits	Search Text	DBs	Time Stamp
5	L5	610	(1 or 2) and (3 or ion near (beam ray stream))	USPA T; US-P GPUB ; EPO; JPO; DERW ENT; IBM TDB	2003/09/0 9 15:25
6	L6	371	(nano nanometer nanoscale nm) with (metal conductor Al W Pt aluminum tungsten platinum) same(3 or ion near (beam ray stream))	USPA T; US-P GPUB ; EPO; JPO; DERW ENT; IBM TDB	2003/09/0 9 15:32
7	L7	741	(nano nanometer nanoscale nm) with (metal conductor Al W Pt aluminum tungsten platinum) same(sensor)	USPA T; US-P GPUB ; EPO; JPO; DERW ENT; IBM TDB	2003/09/0 9 15:32
8	L8	1	5 and 6 and 7	USPA T; US-P GPUB ; EPO; JPO; DERW ENT; IBM TDB	2003/09/0 9 15:34

	L #	Hits	Search Text	DBs	Time Stamp
9	L9	16	6 and 7 not 8	USPA T; US-P GPUB ; EPO; JPO; DERW ENT; IBM TDB	2003/09/0 9 15:33
10	L10	4	5 and 7 not (8 or 9)	USPA T; US-P GPUB ; EPO; JPO; DERW ENT; IBM TDB	2003/09/0 9 15:35
11	L11	13	5 and 6 not (8 or 9 or 10)	USPA T; US-P GPUB ; EPO; JPO; DERW ENT; IBM TDB	2003/09/0 9 15:36
12	L12	33	10 or 9 or 11	USPA T; US-P GPUB ; EPO; JPO; DERW ENT; IBM TDB	2003/09/0 9 15:36

LJ

NOT prior art

	Document ID	Issue Date	Title	Current OR	Inventor
1	US 2003004 0173 A1	8/14/01 4/9/01 3/26/02 7	Fabrication of molecular scale devices using fluidic assembly	438/622	Fonash, Stephen J. et al.

[00564] application \Rightarrow Sensors ... Nanoscale

	Document ID	Issue Date	Title	Current OR	Inventor
1	US 20030143827 A1	20030731	Low area metal contacts for photovoltaic devices	438/597	Wenham, Stuart Ross et al.
2	US 20030047028 A1	20030313	Nanomaterials of composite metal oxides	75/230	Kunitake, Toyoki et al.
3	US 20030036204 A1	20030220	Surface plasmon enhanced illumination system	436/172	Stark, Peter Randolph Hazard et al.
4	US 20030035253 A1	20030220	[0051] GMR Sensor Pt-Mn layers (48.76) [0052] TIB separator Magneto resistance sensors with Pt-Mn transverse and longitudinal pinning layers, and their fabrication method	360/324	Lin, Tsann et al.
5	US 20030020060 A1	20030130	DIV → 4/21/00 PN G14 761409 Nano-structures, process for preparing nano-structures and devices	257/13	Iwasaki, Tatsuya et al.

~~good but pull~~
8

[0011] ... gas sensors ... nanoholes filled w/ metal ...
 [D123] the Al film irradiated FIB → form pore prints at 60nm intervals
 FIB → Ga

	Document ID	Issue Date	Title	Current OR	Inventor
6	US 2003000 2226 A1	20030102	Fabrication method for spin valve sensor with insulating and conducting seed layers	360/314	Lin, Tsann et al.
7	US 2002019 0251 A1	20021219	Thin film materials of amorphous metal oxides	257/43	Kunitake, Toyoki et al.
8	US 2002010 9134 A1	20020815	NANO-STRUCTURES, PROCESS FOR PREPARING NANO-STRUCTURES AND DEVICES Al + PIB → // lines at 100 nm pitch	257/13	Iwasaki, Tatsuya et al.
9	US 2002008 6526 A1	20020704	(AD) Apparatus and a method for forming an alloy layer over a substrate	438/653	Gavish, Ilan
10	US 2002005 6816 A1	20020516	Surface plasmon enhanced illumination system	250/493 .1	Stark, Peter Randolph Hazard

	Document ID	Issue Date	Title	Current OR	Inventor
11	US 2002001 2797 A1	20020131	Multilayer system with protecting layer system and production method	428/408	Bijkerk, Frederik et al.
12	US 6607779 B2	20030819	Nanotechnology for photonic and optical components	427/58	Yadav, Tapesh et al.
13	US 6592725 B2	20030715	Fabrication method for spin valve sensor with insulating and conducting seed layers	204/192.2	Lin, Tsann et al.
14	US 6562523 B1	20030513	Direct write all-glass photomask blanks	430/5	Wu, Che-Kuang et al.

	Document ID	Issue Date	Title	Current OR	Inventor
15	US 6548398 B1	20030415	Production method of semiconductor device and production device therefor	438/622	Yamasaki, Hideaki
16	US 6524756 B1	20030225	Gray scale all-glass photomasks	430/5	Wu, Che-Kuang
17	US 6521098 B1	20030218	I/PB Spots Fabrication method for spin valve sensor with insulating and conducting seed layers	204/192 .11	Lin, Tsann et al.
18	US 6514453 B2	20030204	??(D15) Polymer, including IB treated poly (D16) A new scale thermistor array Thermal sensors prepared from nanostructured powders	264/618	Vigliotti, Anthony et al.
19	US 6476409 B2	20021105	Nano-structures, process for preparing nano-structures and devices	257/13	Iwasaki, Tatsuya et al.

	Document ID	Issue Date	Title	Current OR	Inventor
(Ab) 20	US 6413880 B1	20020702	Strongly textured atomic ridge and dot fabrication	(D7) 438/759	"Rv EBatchy" Baski, Alison et al.
(D4) 21	US 6313905 B1	20011106	Apparatus and method for defining a pattern on a substrate	355/55	Brugger, Juergen P. et al.
(Ab) 22	US 6259350 B1	20010710	Sensor and method for manufacturing a sensor	338/25	Mueller-Fiedler, Roland et al.

(D6) In a preferment... ---
 --- pt layer 23 \rightarrow 100 nm ---- Top sensor
 (D7) The pref. manufac... plasma-etch patterning FB etch

	Document ID	Issue Date	Title	Current OR	Inventor
23	US 6168845 B1 <i>(B) A)</i> cont. med cont. - spec. Ibs dep - spec. Ibs dep	20010102	Patterned magnetic media and method of making the same using selective oxidation	428/65. 5	Fontana, Jr., Robert Edward et al.
24	US 5912044 A <i>skr</i>	19990615	Method for forming thin film capacitors	427/79	Farooq, Mukta Shaji et al.

Pull

	Document ID	Issue Date	Title	Current OR	Inventor
(B8) 25	US 5789320 A <i>JBP et al.</i>	19980804	Plating of noble metal electrodes for DRAM and FRAM	438/678	Andrica cos, Panayot is Constantinou et al.
(B14) 26	US 5741557 A	19980421	Method for depositing metal fine lines on a substrate	427/469	Corbin, Antoine et al.
27	US 5227364 A	19930713	Method of forming patterned oxide superconducting films and Josephson junction devices by using an aqueous alkaline solution	505/329	Fujiwara, Shuji et al.

	Document ID	Issue Date	Title	Current OR	Inventor
28	US 5192714 A	19930309	Method of manufacturing a multilayered metallization structure in which the conductive layer and insulating layer are selectively deposited	438/631	Suguro, Kyoichi et al.
29	AB, from metal beam FEB US 4908226 A	19900313	Selective area nucleation and growth method for metal chemical vapor deposition using focused ion beams	427/526	Kubena, Randall L. et al.

Pull

	Document ID	Issue Date	Title	Current OR	Inventor
30	US 4853341 A	19890801	Process for forming <u>electro</u> des for semiconductor devices using focused ion beams	438/625	Nishioka, Tadashi et al.
31	US 4782302 A	19881101	Detector and energy analyzer for energetic-hydrogen in beams and plasmas	324/71.3	Bastasz, Robert J. et al.
32	US 4686162 A	19870811	Optically structured filter and process for its production	430/5	Stangl, Gunther et al.
33	US 4001061 A	19770104	Single lithography for multiple-layer bubble domain devices	427/96	Ahn, Kie Y. et al.